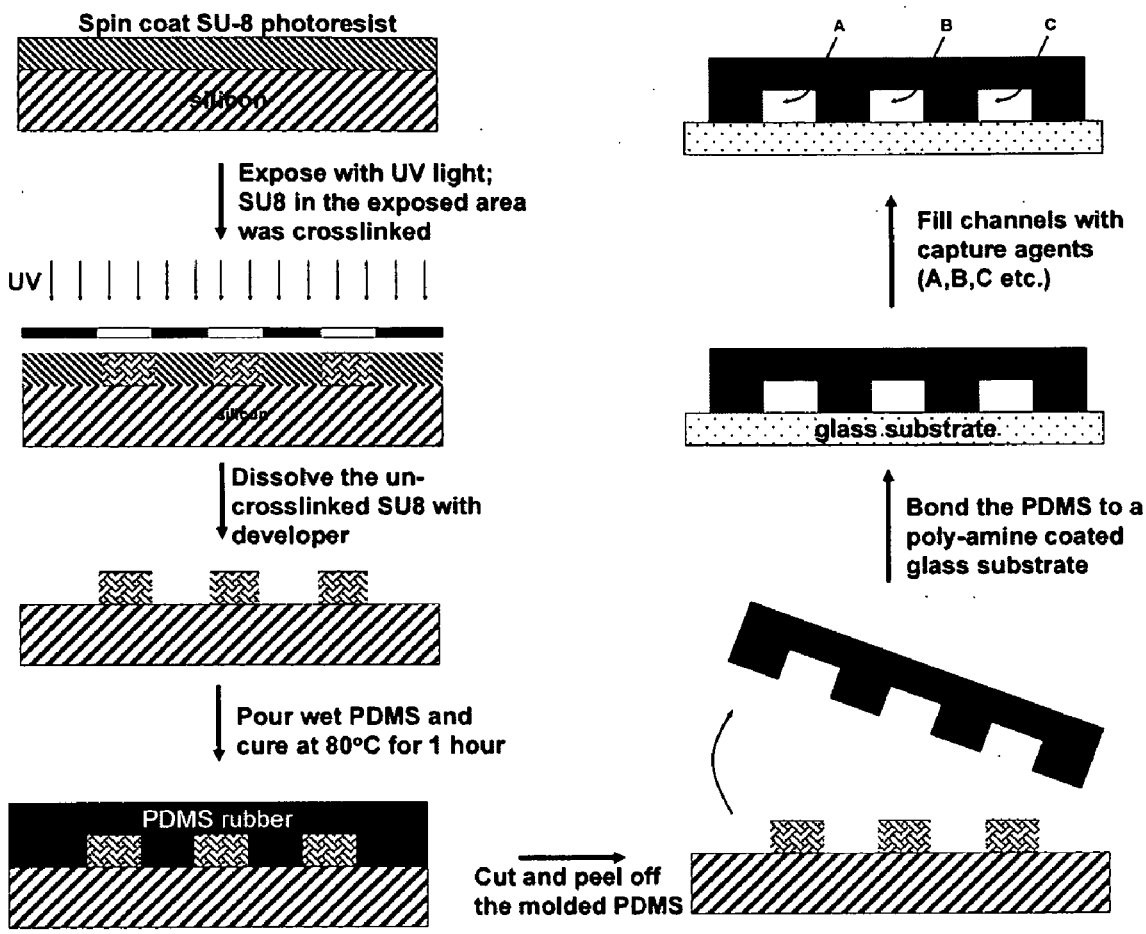
Spin coat SU-8 photoresist
silicon
Expose with UV light;
SU8 in the exposed area
was crosslinked
UV
silicon
Dissolve the un-
crosslinked SU8 with
developer
Pour wet PDMS and
cure at 80°C for 1 hour
PDMS rubber
Cut and peel off
the molded PDMS
Bond the PDMS to a
poly-amine coated
glass substrate
glass substrate
Fill channels with
capture agents
(A,B,C etc.)
A
B
C

FIG. 4